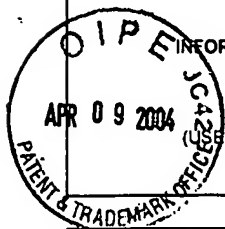


FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.  
ASMEX.328AAPPLICATION NO.  
10/074,633INFORMATION DISCLOSURE STATEMENT  
BY APPLICANTAPPLICANT  
Michael A. ToddFILING DATE  
February 11, 2002GROUP  
2814

(USE FOR SEVERAL SHEETS IF NECESSARY)



## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
LP	5,389,570	02/14/95	Shiozawa			

## FOREIGN PATENT DOCUMENTS

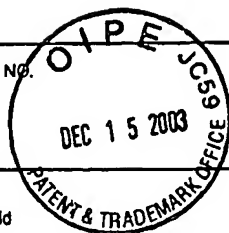
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

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EXAMINER	<i>Long Pham</i>	DATE CONSIDERED	<i>7/7/04</i>
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.			

FORM PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. ASMEX.328A	APPLICATION NO. 10/074,833
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (USE SEVERAL SHEETS IF NECESSARY)		APPLICANT Michael A. Todd	GROUP 2814
		FILING DATE February 11, 2002	



U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
EP	1.	5,192,714	03/09/93	Suguro et al.			
	2.	5,194,398	03/16/93	Miyachi et al.			
	3.	5,461,250	10/24/95	Burghartz et al.			
	4.	5,563,093	10/08/96	Koda et al.			
	5.	5,869,389	02/09/99	Ping et al.			
	6.	6,013,922	01/11/00	Ueda et al.			
	7.	6,365,479	04/02/02	U'Ren			

FOREIGN PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)	

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EXAMINER	<i>Long Phan</i>	DATE CONSIDERED	<i>7/7/04</i>
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2814

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
LP	1.	5,389,398	02/14/95	Suzuki et al.	427	130	
	2.	5,698,771	12/16/97	Shields et al.	73	31.05	
	3.	6,228,181	05/08/01	Yamamoto et al.	148	33.5	
	4.	6,326,311	12/04/01	Ueda et al.	438	694	
	5.	6,455,892	09/24/02	Okuno et al.	257	328	
	6.	6,613,695	09/02/03	Pomarede et al.	438	767	

## FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO

EXAMINER  
INITIAL

## OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

LP	7.	Ikoma et al., Growth of Si/3C-SiC/Si(100) heterostructures by pulsed supersonic free jets, Applied Physics Letters, Volume 75, No. 25, Pp. 3977-3979, December 1999					

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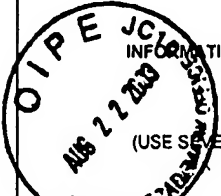
EXAMINER

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DATE CONSIDERED

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		FILING DATE February 11, 2002	GROUP 2814

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
1. LP	5,214,002	05/25/93	Hayashi et al.			
2. LP	5,356,821	10/18/94	Naruse et al.			
3. LP	5,471,330	11/28/95	Sarma			
4. LP	6,103,600	08/15/00	Ueda et al.			

## FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
5. LP	11317530	16-11-99	Japan (abstract)			X	
6. LP	EP 0368651 A2	16-05-90					
7. LP	EP 0486047 A2	20-05-92					
8. LP	EP 0747974 A2	11-12-96					
9. LP	EP 1065728 A2	03-01-01					
10. LP	GB 2332564 A	23-06-99	United Kingdom				

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)
11. LP	Olivares, J. et al.; "Solid-phase crystallization of amorphous SiGe films deposited by LPCVD on SiO <sub>2</sub> and glass," Thin Solid Films 337 (1999) pp. 51-54.

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EXAMINER	Long Pham	DATE CONSIDERED	7/7/04
<p>*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.</p>			

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2812

(USE SEVERAL SHEETS IF NECESSARY)



## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
LP	US 2002/0098627 A1	07/25/02	Pomarede et al.	438	149	08/31/01

## FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

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## OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)


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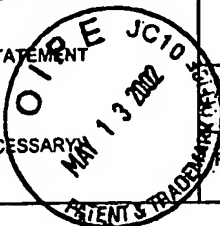
Long Pham

DATE CONSIDERED

7/11/04

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FORM PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. ASMEX.328A	APPLICATION NO. 10/074,633
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT Michael A. Todd	
(USE SEVERAL SHEETS IF NECESSARY)		FILING DATE February 11, 2002	GROUP 2812



FOREIGN PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
LP		60043485 A	3/8/85	Japan			Abstract	
		61153277 A	7/11/86	Japan			Abstract	
		62076612 A	4/8/87	Japan			Abstract	
		63003414 A	1/8/88	Japan			Abstract	
		63003463 A	1/8/88	Japan			Abstract	
		01217956 A	8/31/89	Japan			Abstract	
		01268064 A	10/25/89	Japan			Abstract	
		02155225 A	6/14/90	Japan			Abstract	
		03091239 A	4/16/91	Japan			Abstract	
		03185817 A	8/13/91	Japan			Abstract	
		03187215 A	8/15/91	Japan			Abstract	
		03292741 A	12/24/91	Japan			Abstract	
		04323834 A	11/13/92	Japan			Abstract	
		05021378 A	1/29/93	Japan			Abstract	
		05062911 A	3/12/93	Japan			Abstract	
		07249618 A	9/26/95	Japan			Abstract	
		08242006 A	9/17/96	Japan			Abstract	
		S60-43485	3/8/85	Japan (Patent Disclosure)			X	
		H 02-155225	6/14/90	Japan (Patent Disclosure)			X	
		H3-185817	8/13/91	Japan (Patent Disclosure)			X	
		H3-187215	8/15/91	Japan (Patent Disclosure)			X	
		H3-91239	4/16/91	Japan (Patent Disclosure)			X	
		H5-62911	3/12/93	Japan (Patent Disclosure)			X	

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050702

EXAMINER <i>Long Pham</i>	DATE CONSIDERED <i>7/1/04</i>
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	